

Lesson 9

Photodetectors

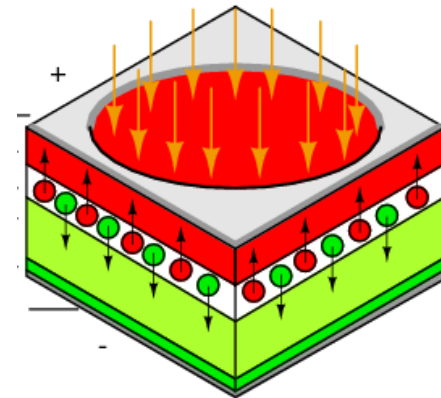
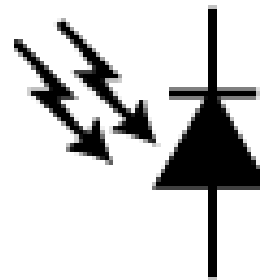
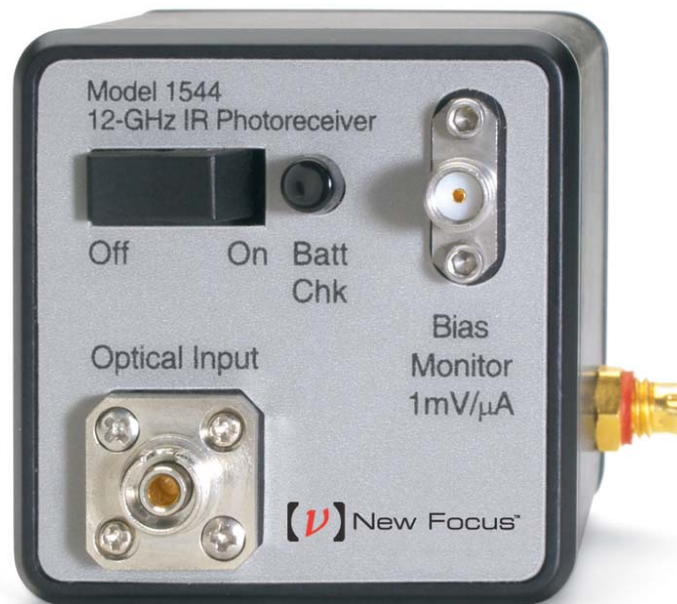
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Motivation and usage

- Modulators: E/O conversion
- PDs: convert optical signal to electrical signal
 - **O/E conversion**



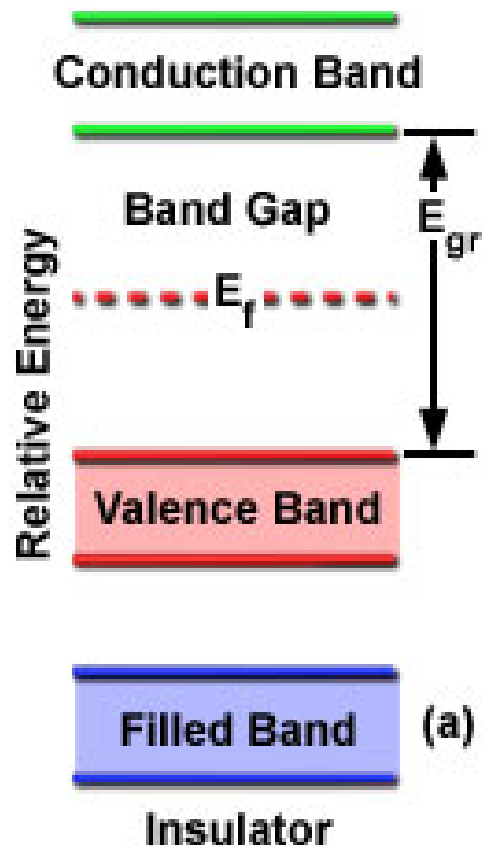


Outline

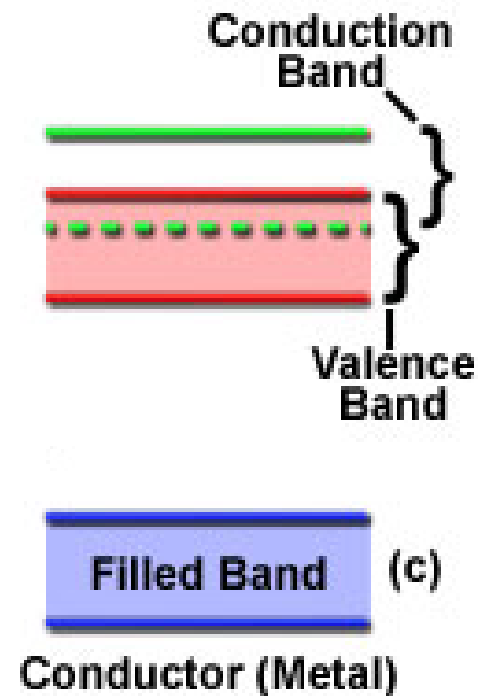
- Concept of semiconductor and energy bandgap
- pn junction
- Photodetector types
- Quantum efficiency

Materials classified by “bandgap”

- Insulator
- Conductor
- Semiconductor

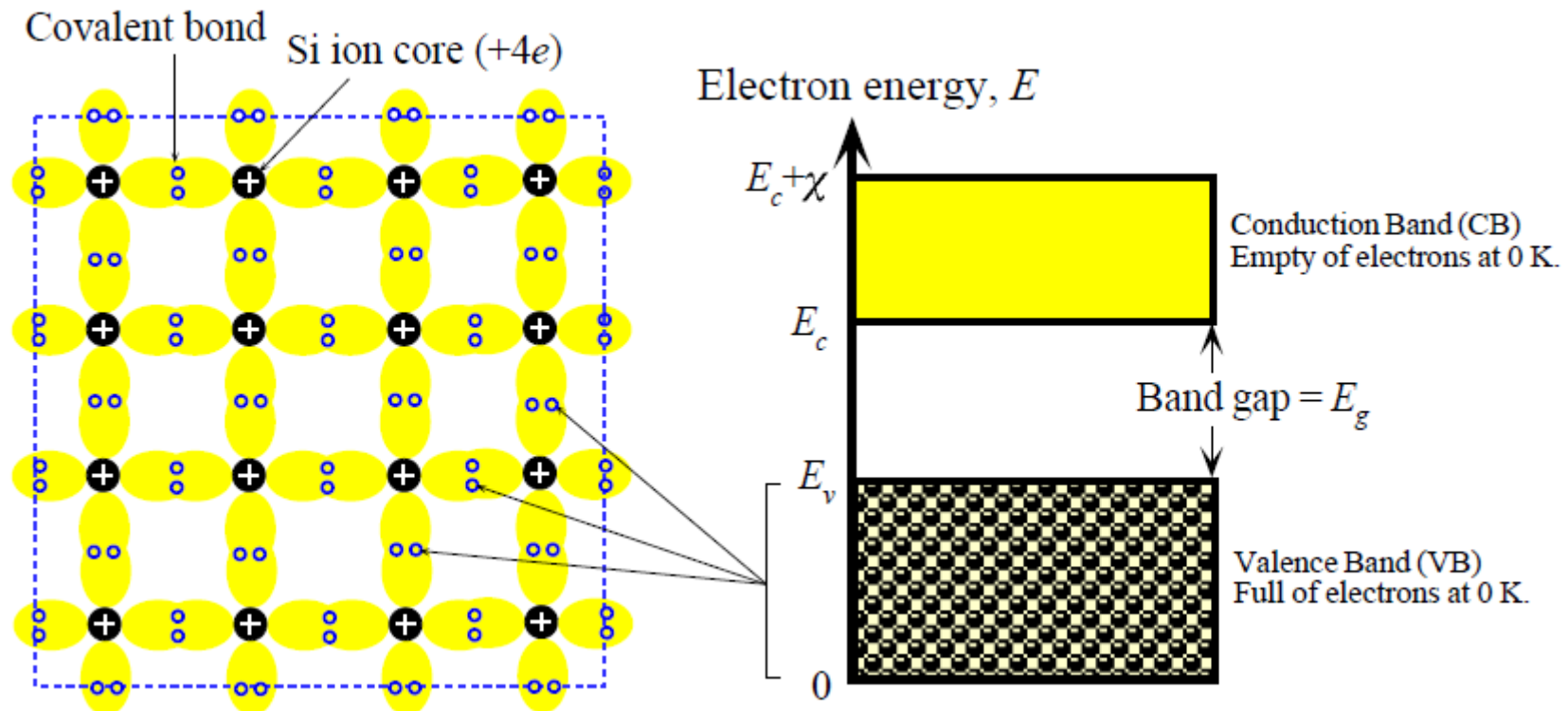


Energy Band Gaps in Materials



Energy bandgap of semiconductor

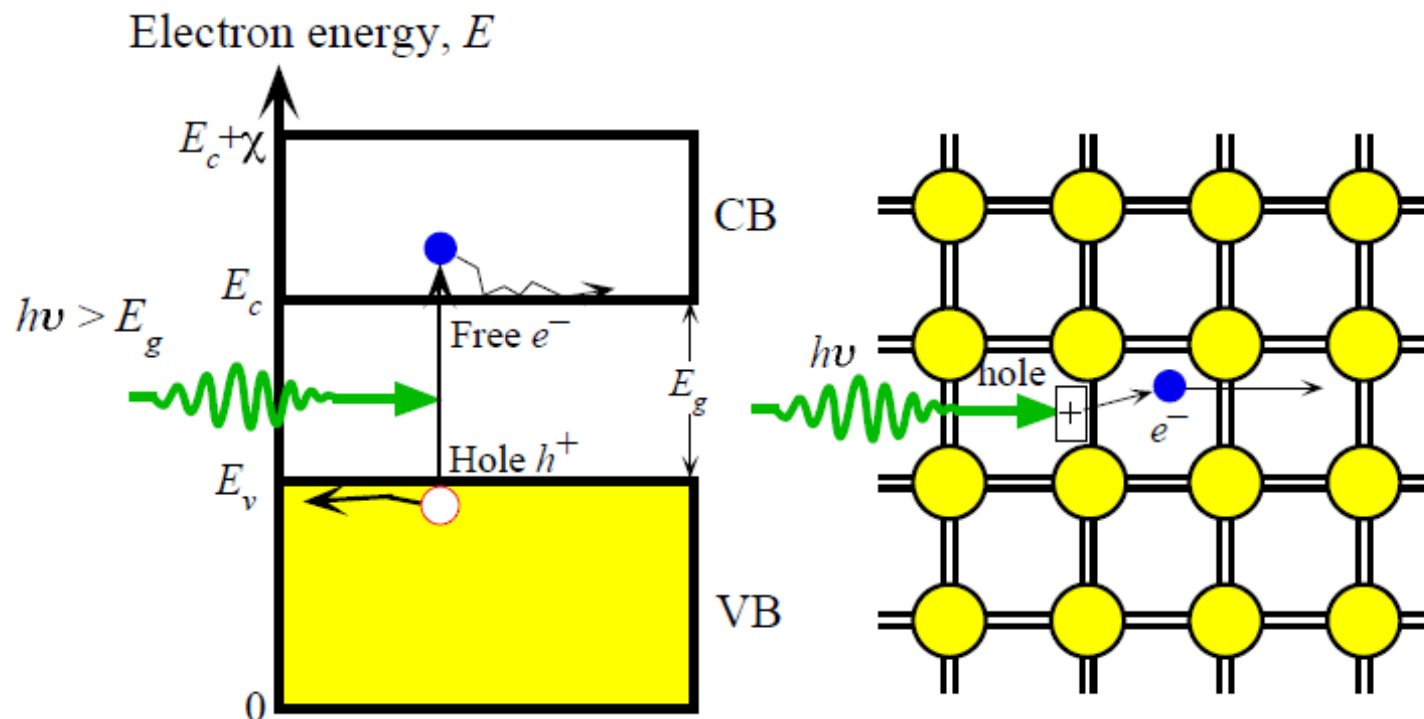
- Lattice defined





A photon can excite an electron: O/E conversion

- The photon energy needs to be greater than E_g
- The excited **free** electron-hole pair can wander freely
- Free electron and hole both contribute to photocurrent



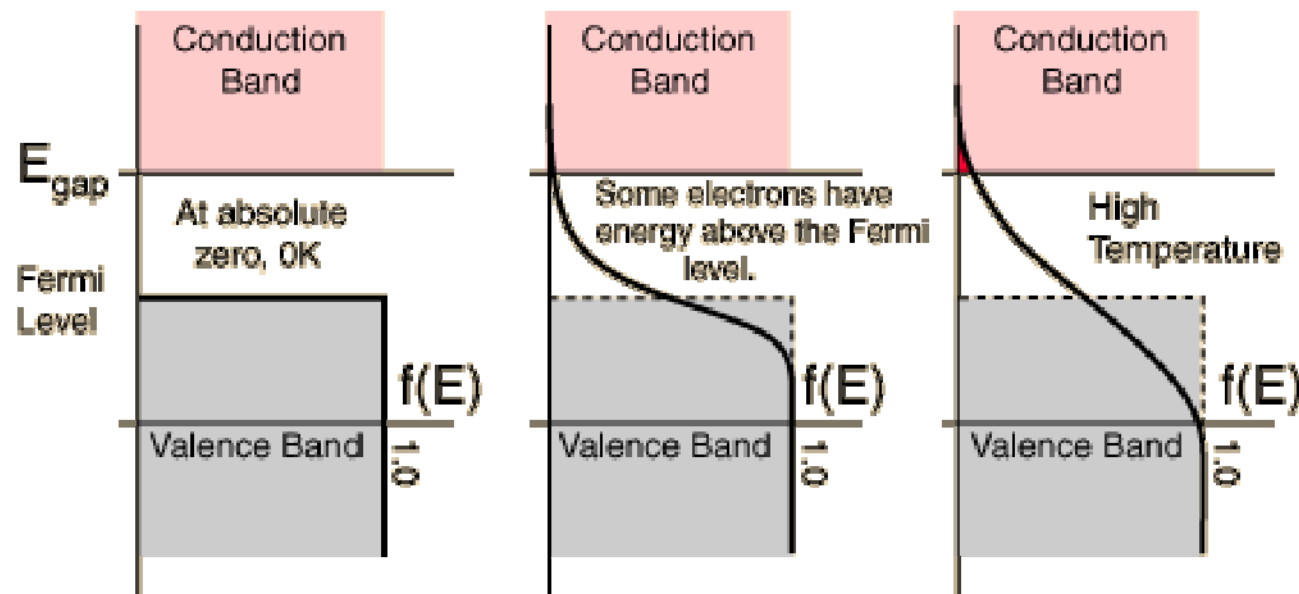


The Fermi level

- Determines the concentration of electron and hole

$$f(E) = \left[1 + \exp\left(\frac{E - E_f}{k_B T}\right) \right]^{-1}$$

$$f(E_f) = 0.5$$



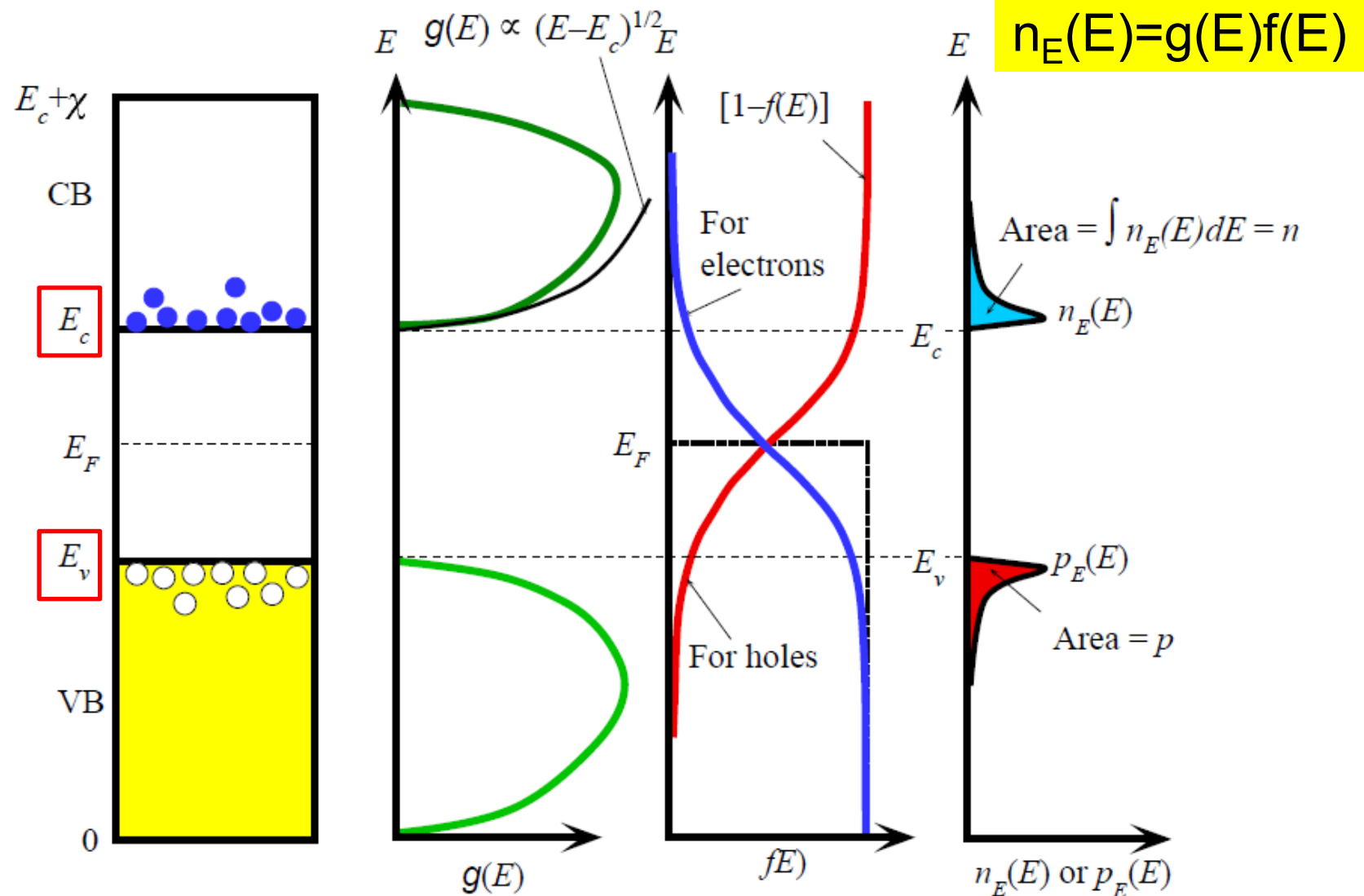
No electrons can be above the valence band at 0K, since none have energy above the Fermi level and there are no available energy states in the band gap.

At high temperatures, some electrons can reach the conduction band and contribute to electric current.

Energy density

- Number of carriers per energy per volume

$g(E)$: density of state





Number of carriers

- When $(E - E_f) \gg k_B T$

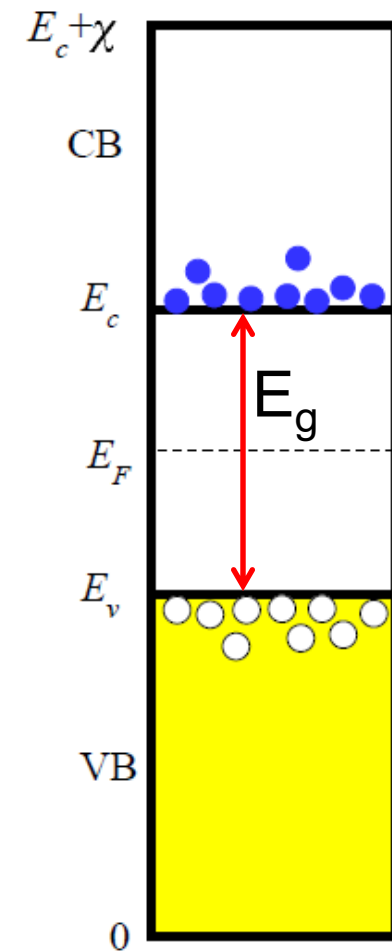
N_c, N_v : effective DOS

$$f(E) = \left[1 + \exp\left(\frac{E - E_f}{k_B T}\right) \right]^{-1} \rightarrow \exp\left[-\frac{(E - E_f)}{k_B T}\right]$$

$$n = N_c \exp\left[-\frac{(E_c - E_f)}{k_B T}\right], N_c = 2 \left[\frac{2\pi m_e^* k_B T}{h^2} \right]^{3/2}$$

$$p = N_v \exp\left[-\frac{(E_f - E_v)}{k_B T}\right], N_v = 2 \left[\frac{2\pi m_h^* k_B T}{h^2} \right]^{3/2}$$

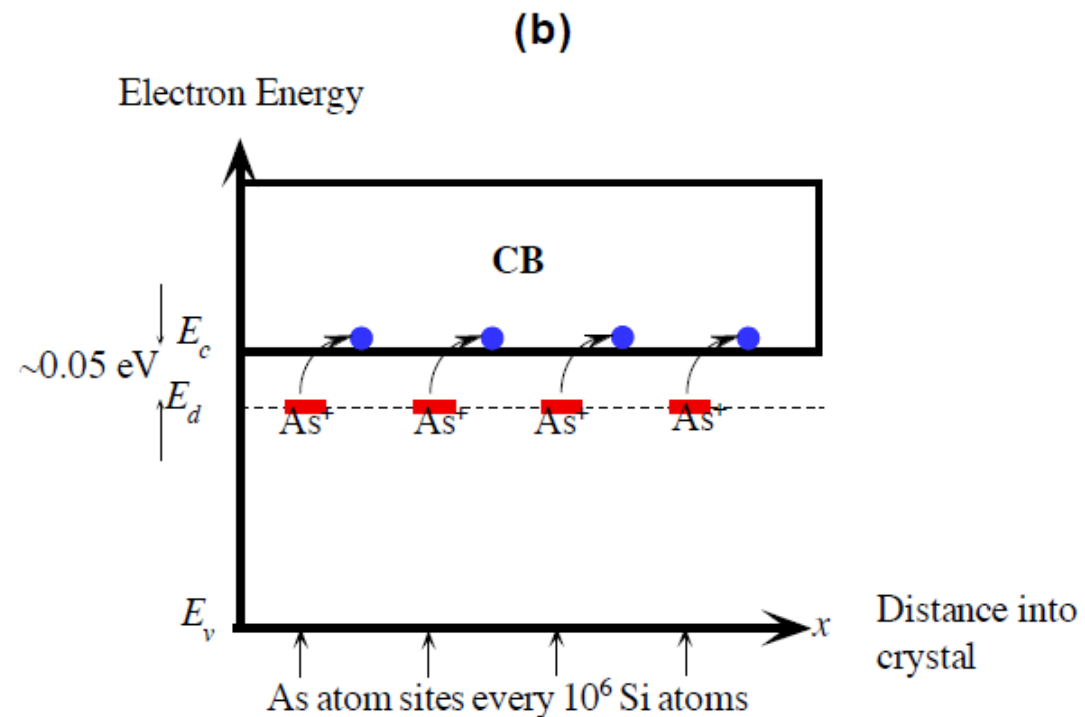
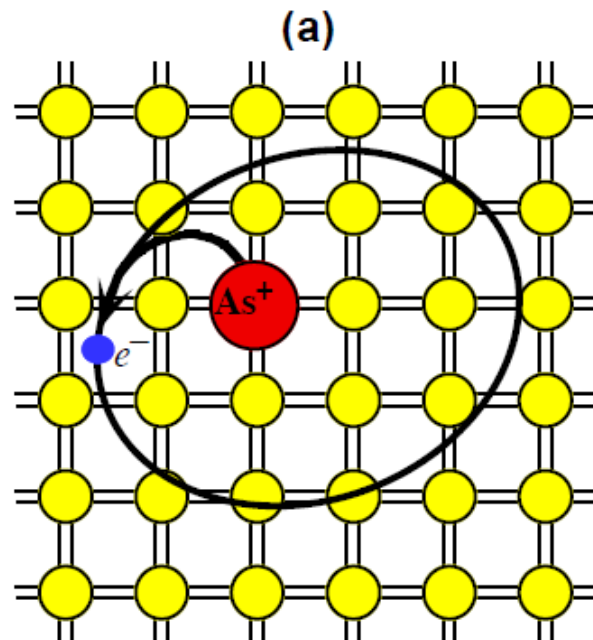
$$np = N_c N_v \exp\left[-\frac{E_g}{k_B T}\right] = n_i^2$$



Changing the Fermi level

- Doping impurities with excess electrons (donor) N_d
 - Example: As into Si
- n-type semiconductor

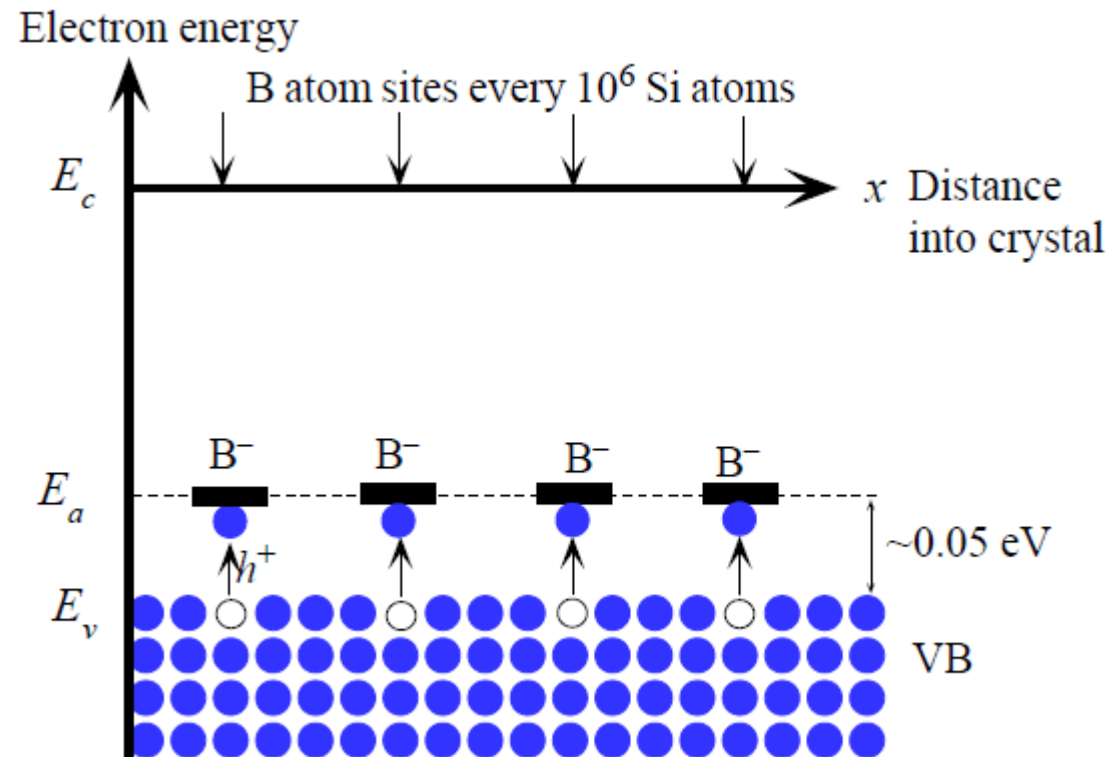
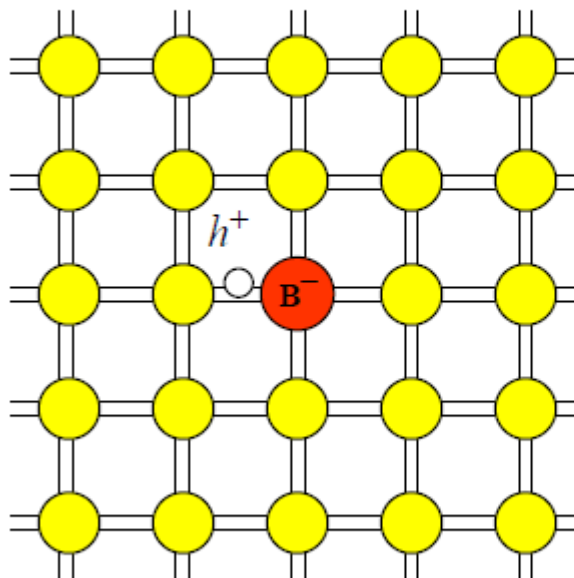
$$n \simeq N_d, \quad p = \frac{n_i^2}{N_d}$$



Changing the Fermi level

- Doping impurities with excess hole (acceptor) N_a
 - Example: B into Si
- p-type semiconductor

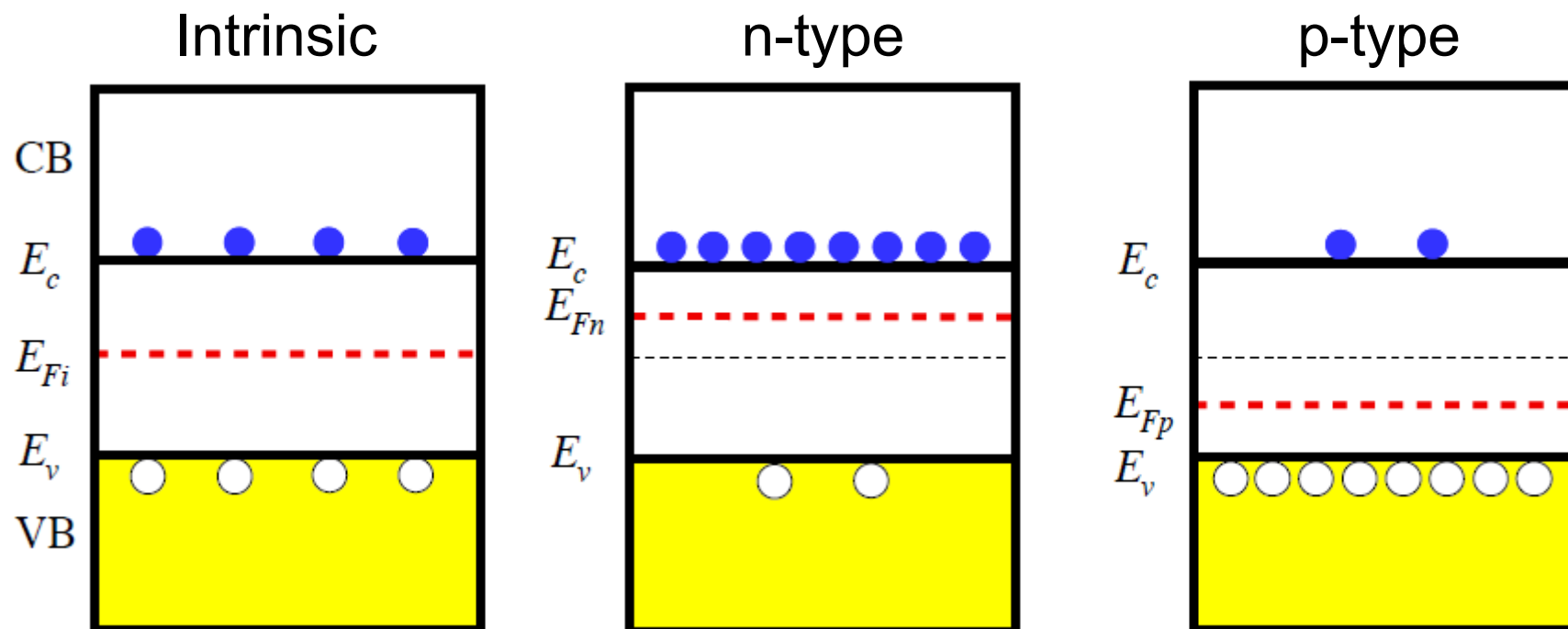
$$p \approx N_a, \quad n = \frac{n_i^2}{N_a}$$





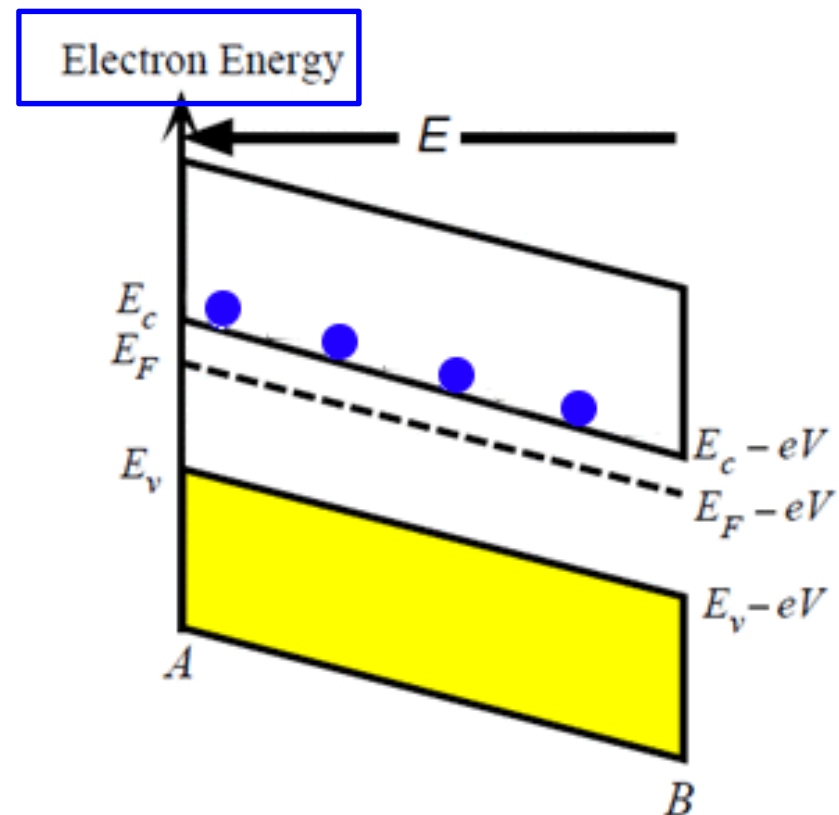
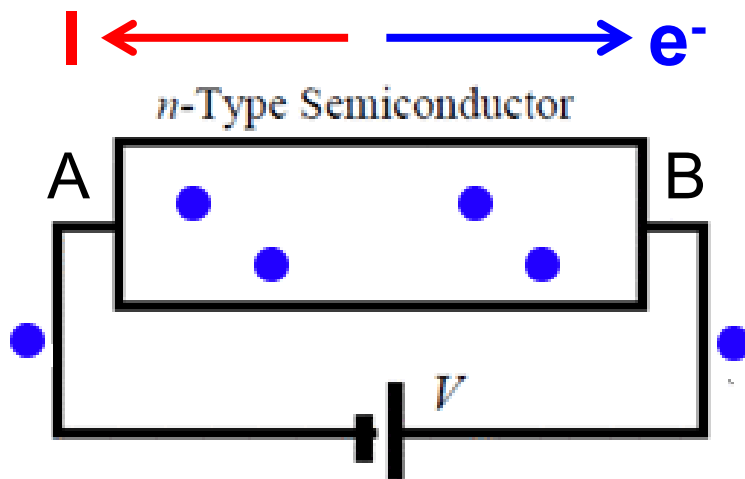
Energy band diagrams for semiconductors

- Classified according to the Fermi level



When you apply an external field

- Bending of the band diagram
- Positive voltage \Leftrightarrow lower electron energy
- Electron flow: reverse direction of current flow

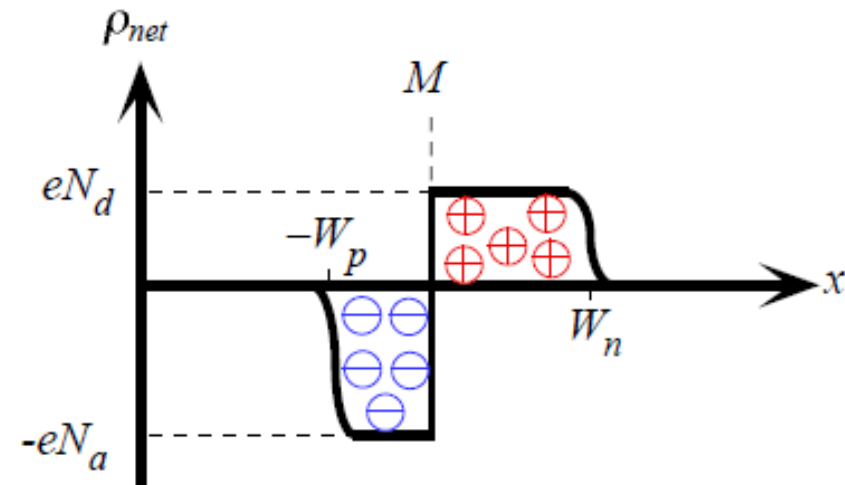
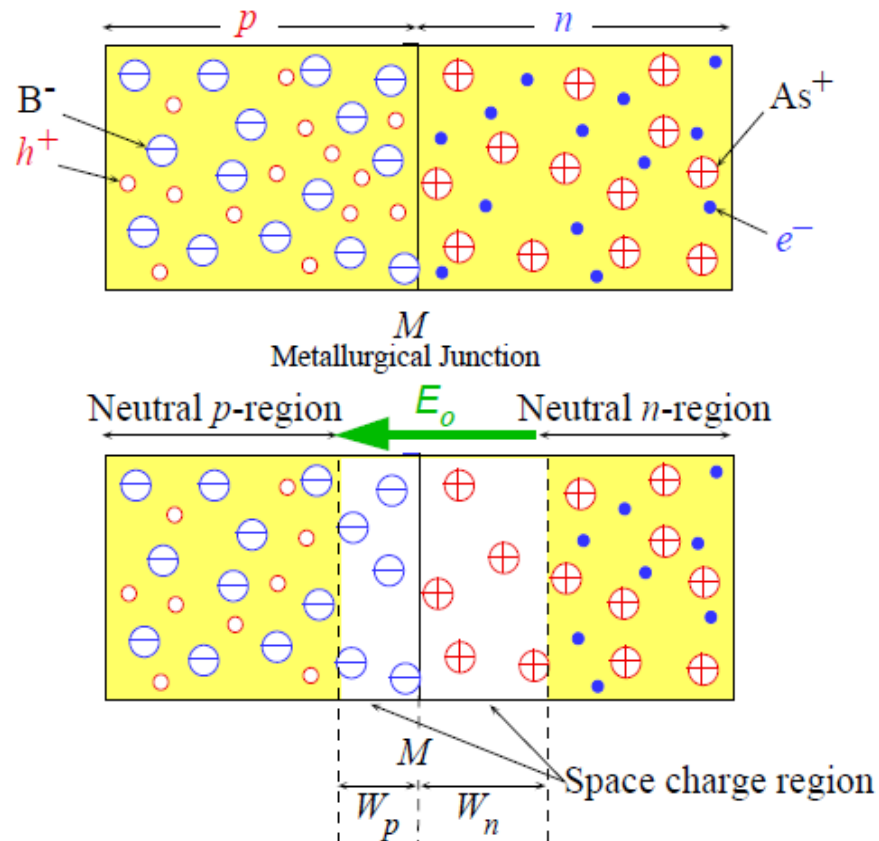




- Concept of semiconductor and energy bandgap
- pn junction
 - Depletion region
 - Built-in voltage
 - Biasing
- Photodetector types
- Quantum efficiency

pn-junction

- Formation of **depletion region** or **space-charge layer**





pn-junction

- Gives rise to a built-in voltage V_0

$$\frac{\partial \vec{E}}{\partial x} = \frac{\rho_{net}(x)}{\epsilon} \Rightarrow E = \int \frac{\rho_{net}(x)}{\epsilon} \cdot dx$$

$$E_0 = -\frac{qN_D W_n}{\epsilon} = -\frac{qN_A W_p}{\epsilon}$$

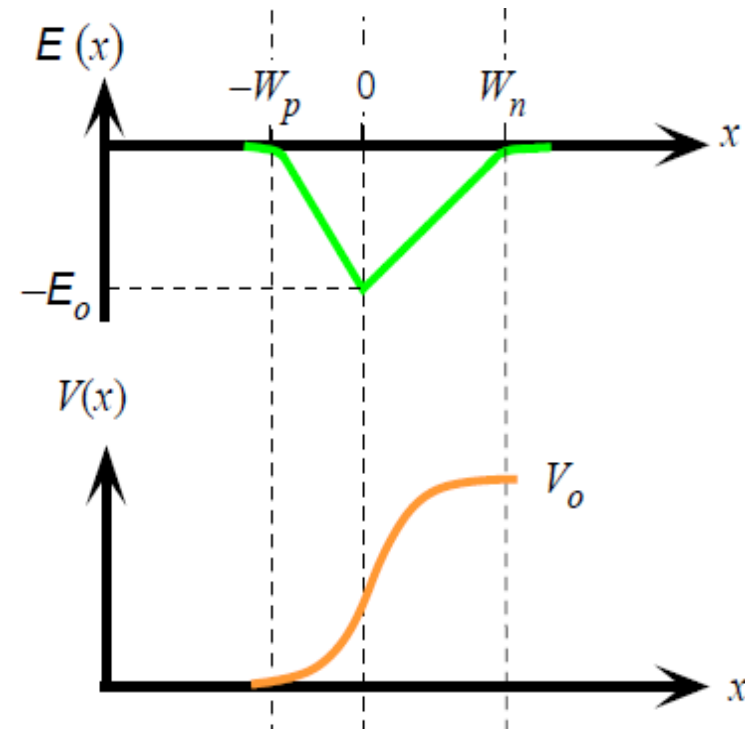
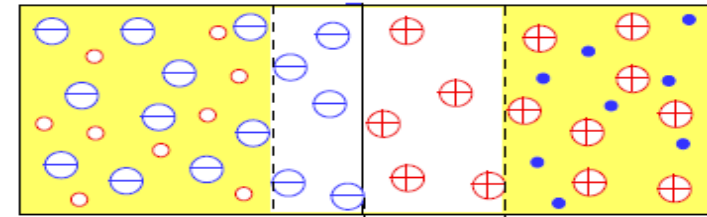
$$\vec{E} = -\nabla V = -\frac{\partial V}{\partial x} \Rightarrow V = -\int E \cdot dx$$

$$W_p = W_0 \frac{N_D}{N_A + N_D}; W_n = W_0 \frac{N_A}{N_A + N_D}$$

(charge neutrality)

$$V_0 = -\frac{1}{2} E_0 W_0 = \frac{qN_A N_D W_0^2}{2\epsilon(N_A + N_D)}$$

$$\nabla \cdot \vec{D} = \rho_{net}$$





Built-in voltage

- Detailed derivations

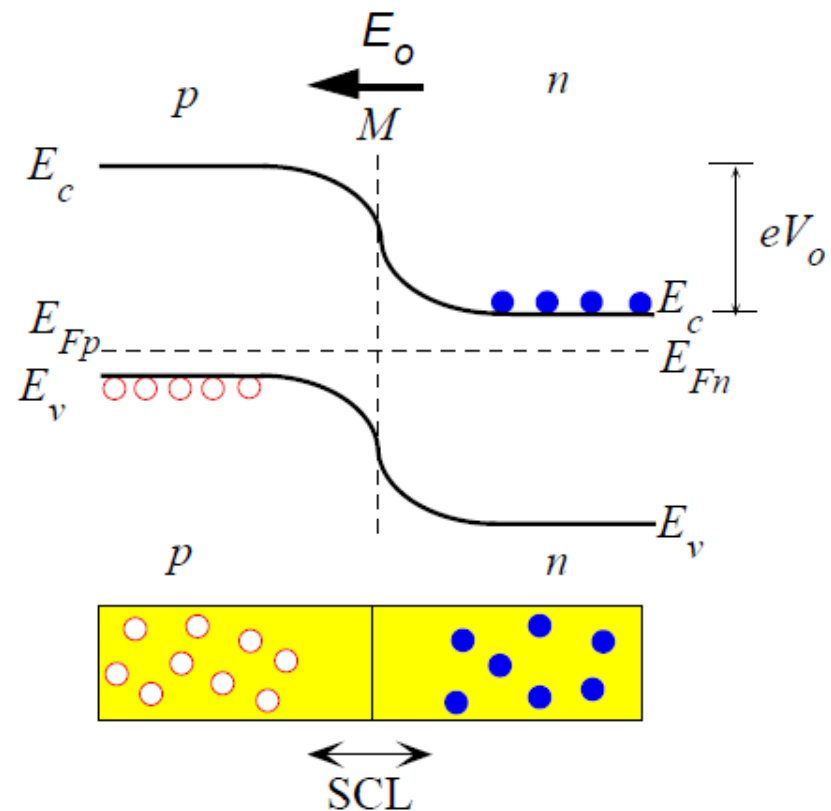
$$qV_0 = [E_{cp} - E_{fp}] - [E_{cn} - E_{fn}]$$

$$\frac{n_i^2}{N_A} = N_C \exp\left[\frac{-(E_{cp} - E_{fp})}{kT}\right] \Rightarrow (E_{cp} - E_{fp}) = kT \ln\left(\frac{N_A N_C}{n_i^2}\right)$$

$$N_D = N_C \exp\left[\frac{-(E_{cn} - E_{fn})}{kT}\right]$$

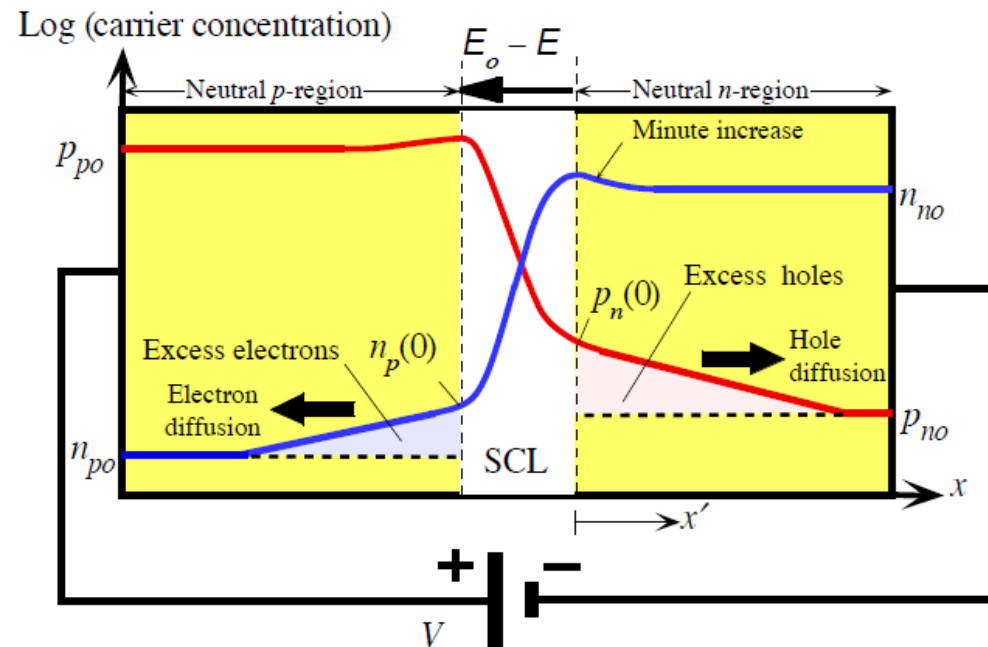
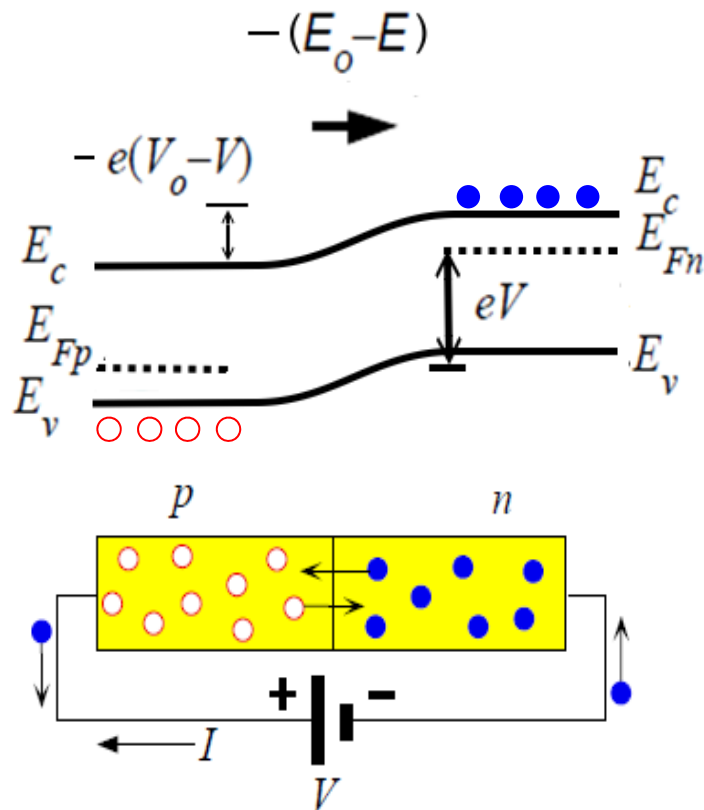
$$\Rightarrow (E_{cn} - E_{fn}) = kT \ln\left(\frac{N_C}{N_D}\right)$$

$$V_0 = \frac{kT}{q} \ln\left(\frac{N_A N_D}{n_i^2}\right) = \frac{qN_A N_D W_0^2}{2\epsilon(N_A + N_D)}$$



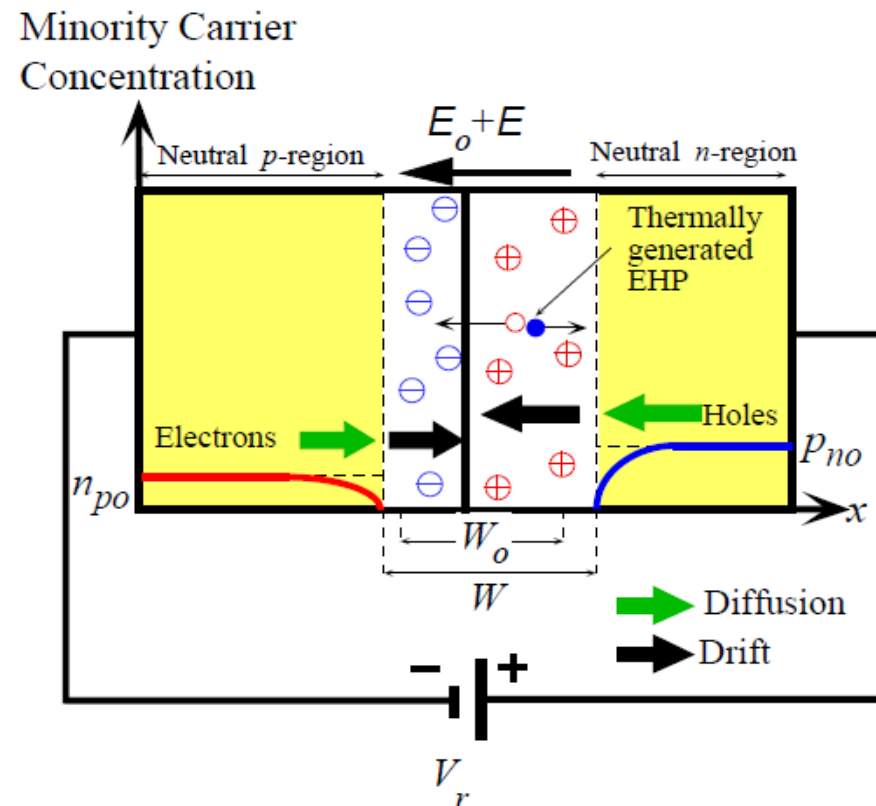
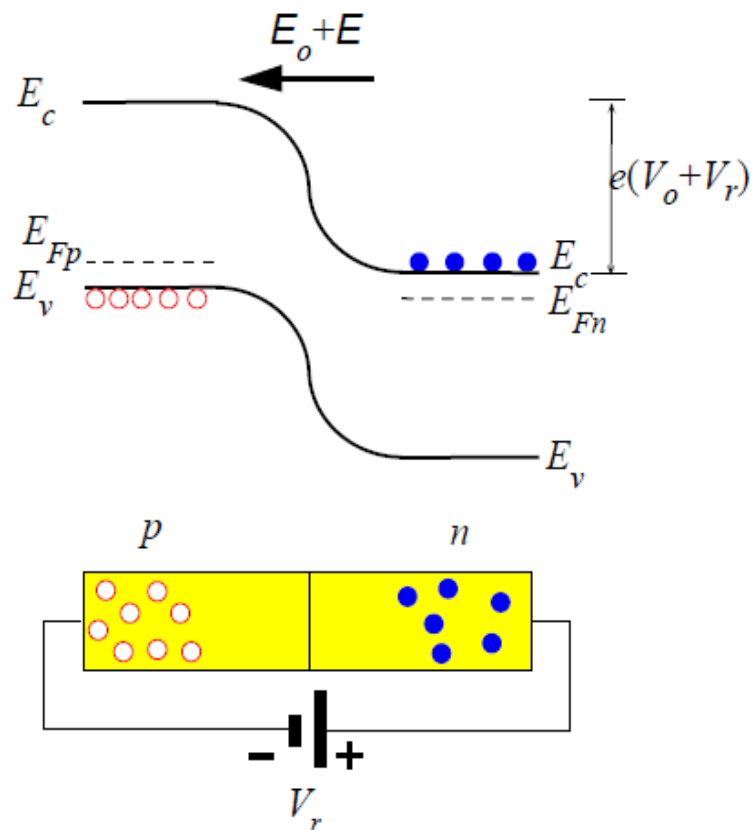
Forward-bias the pn-junction

- Huge electrical current
 - Is this what we want?



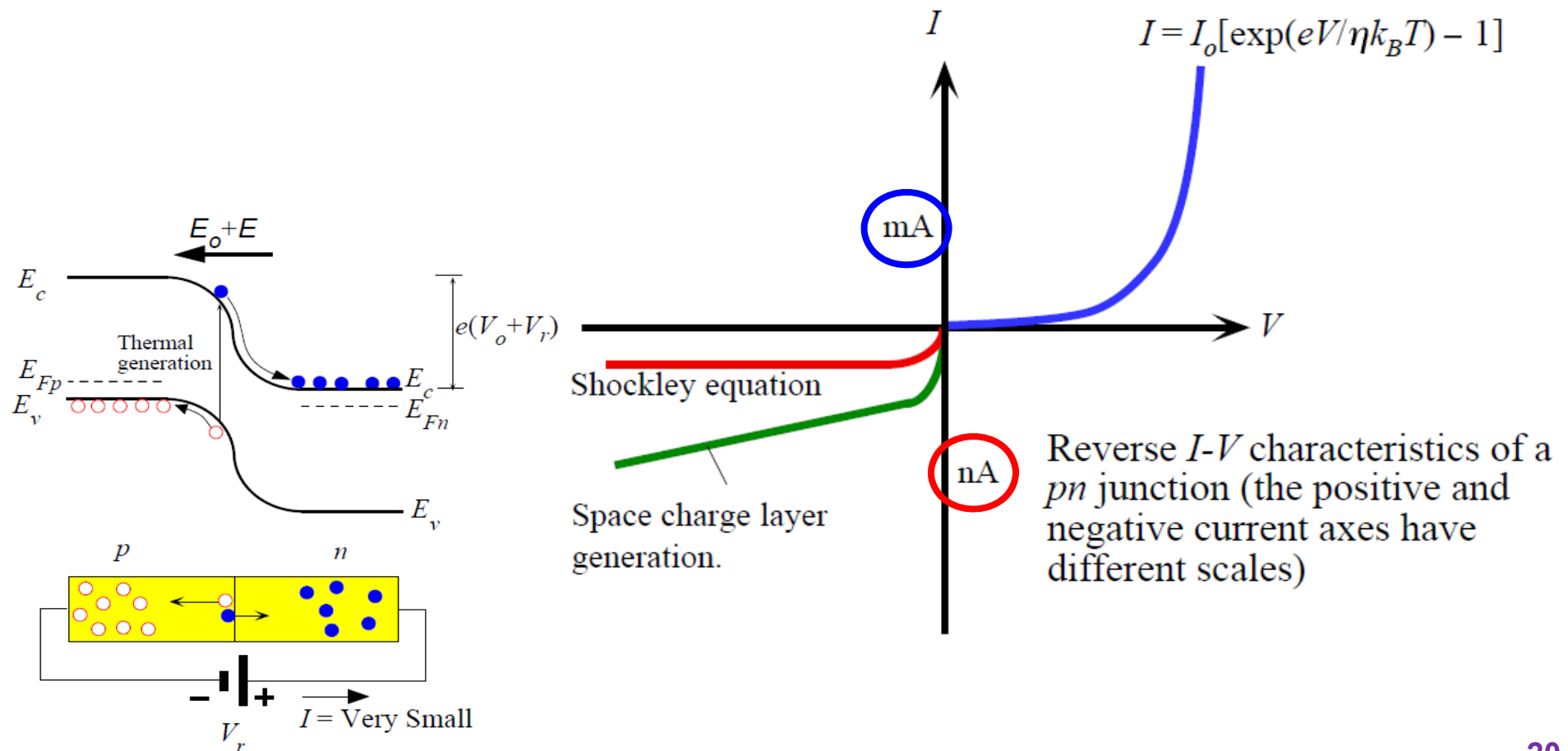
Reverse-bias the pn-junction

- For photodetection
 - Current only generated by photons
 - Increases depletion length



Current vs. bias voltage

- Diode characteristic





- Concept of semiconductor and energy bandgap
- pn junction

- Photodetector types
 - Absorption coefficient and materials
 - pn-junction photodiode
 - pin photodiode
 - Avalanche photodiode
 - Heterojunction photodiodes
 - Photoconductive photodiodes

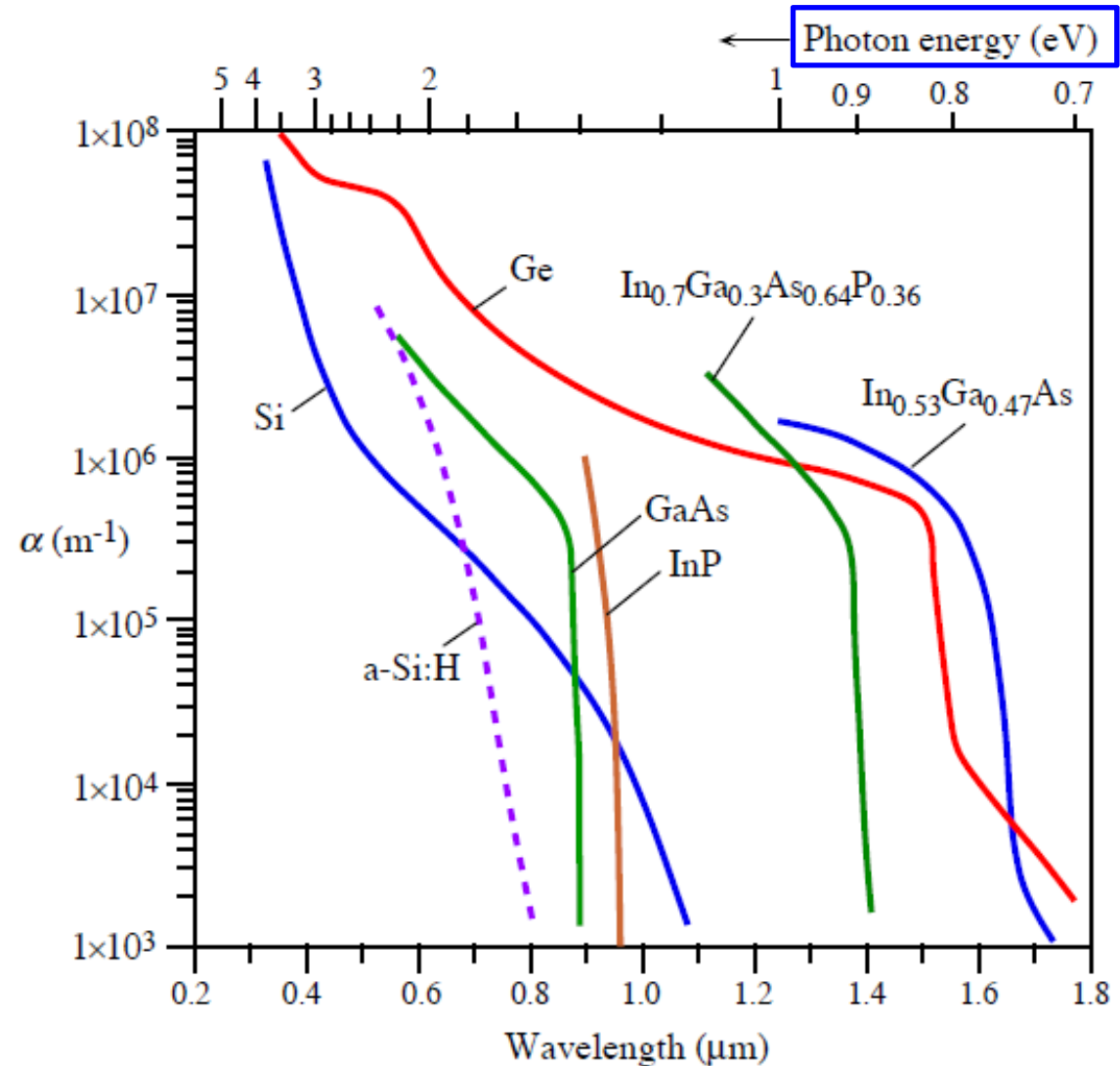
- Quantum efficiency



Absorption coefficients of various materials

- Si: 400~1100 nm
- InGaAs: 900~1700 nm
- eV

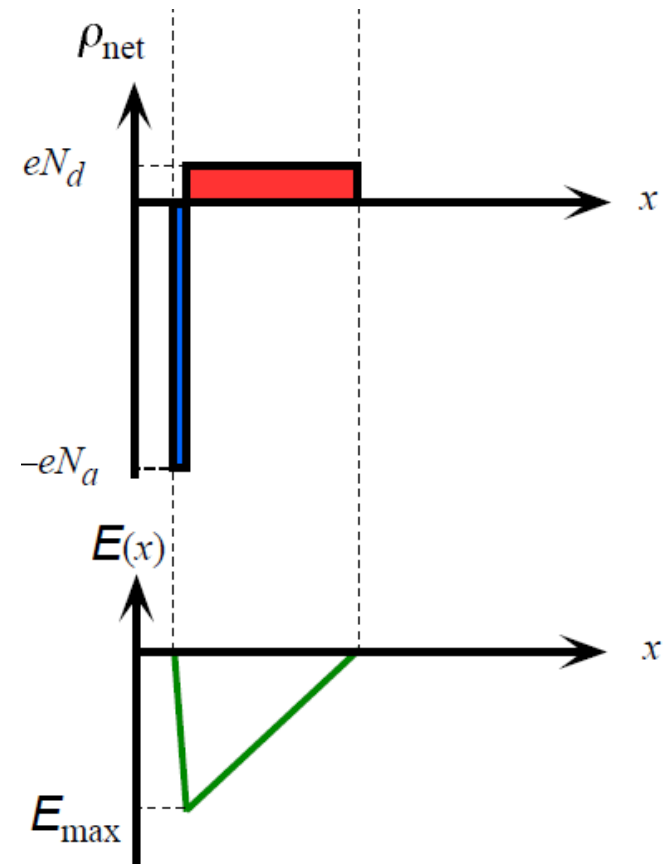
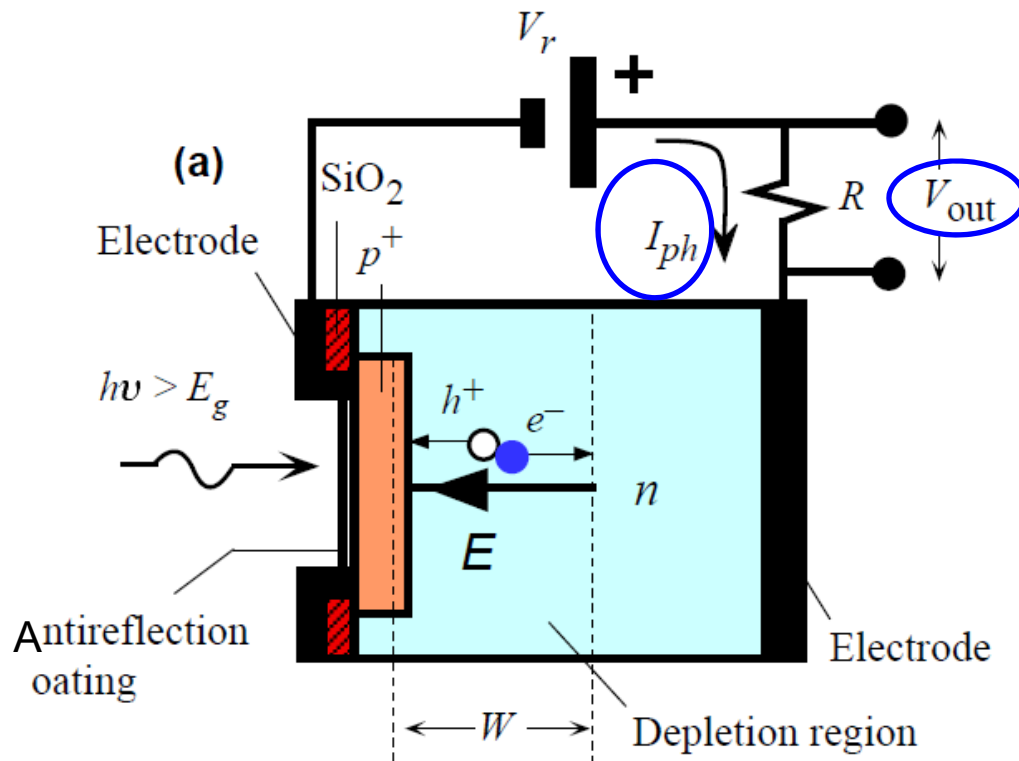
$$\frac{h\nu}{q} = \frac{hc}{q\lambda} \doteq \frac{1.24}{\lambda(\mu\text{m})}$$



pn photodiodes (PD)

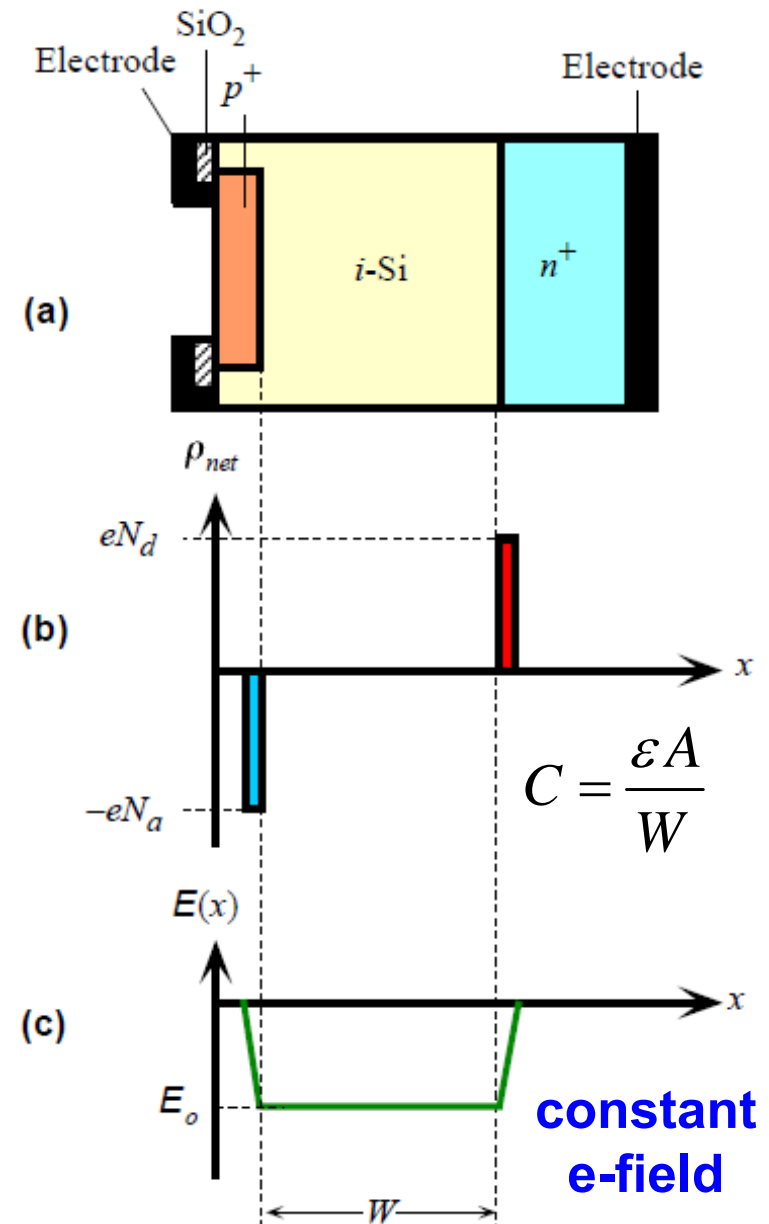
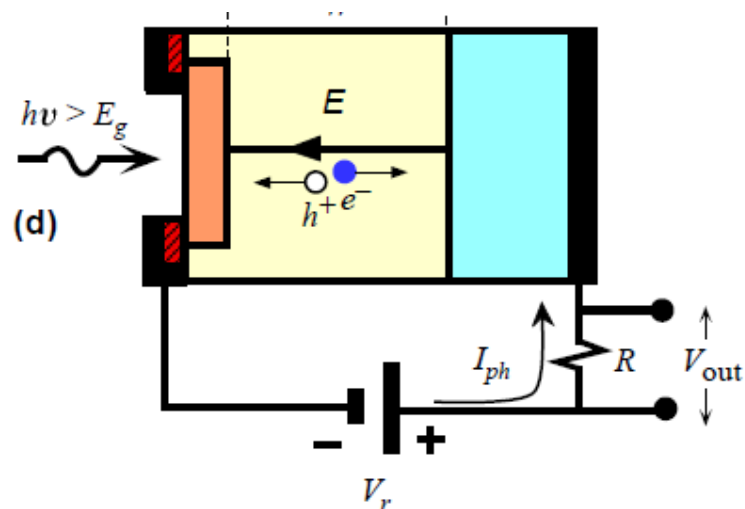
- Reverse-bias a pn-junction
- p+ layer thin, almost entirely depletion
- Photocurrent \rightarrow voltage
- **Capacitance** depends on bias

$$C = \frac{\epsilon A}{W}$$



pin PDs

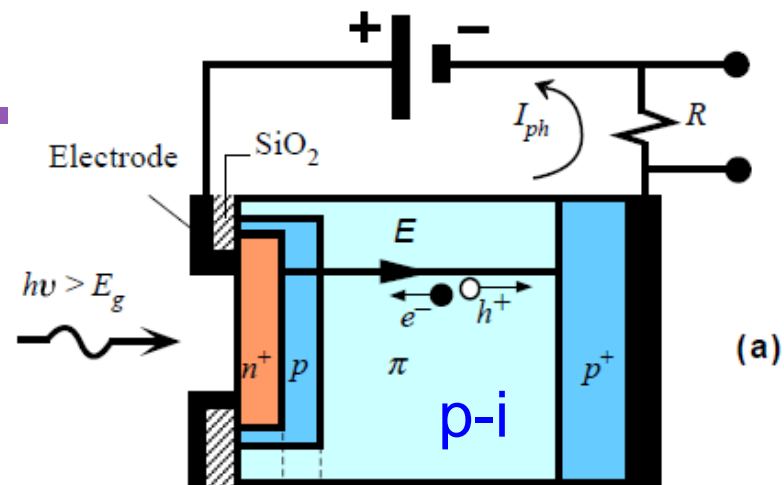
- A sandwiched intrinsic layer
 - Reduce capacitance
 - Longer absorption length
 - Constant e-field
 - Fixed junction capacitance



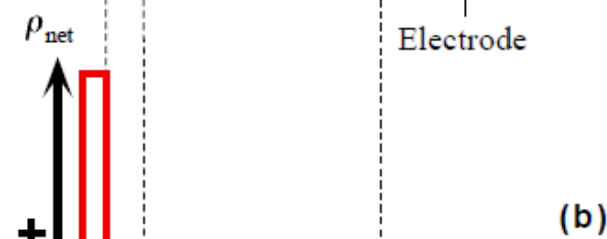


Avalanche PDs

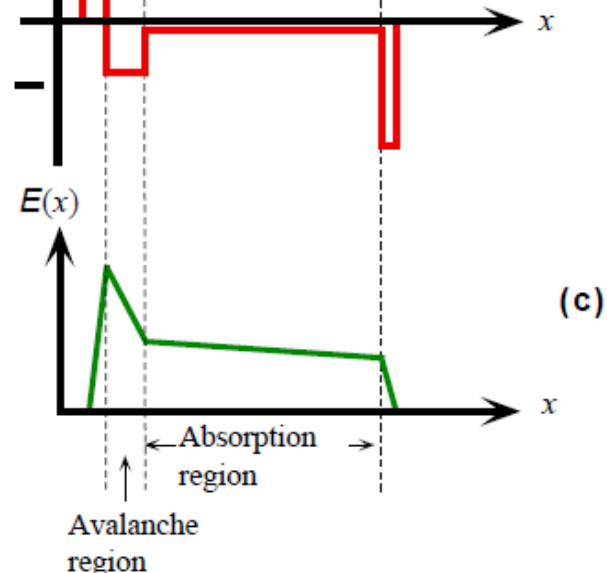
- Current **multiplication/gain**
 - Acceleration \rightarrow impact ionization



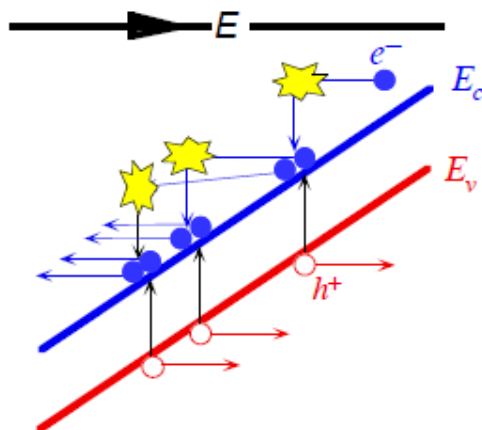
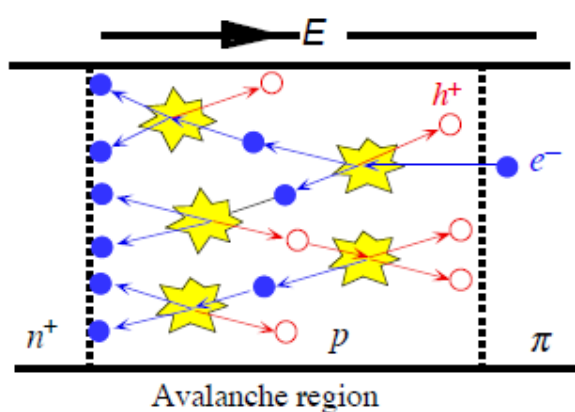
(a)



(b)

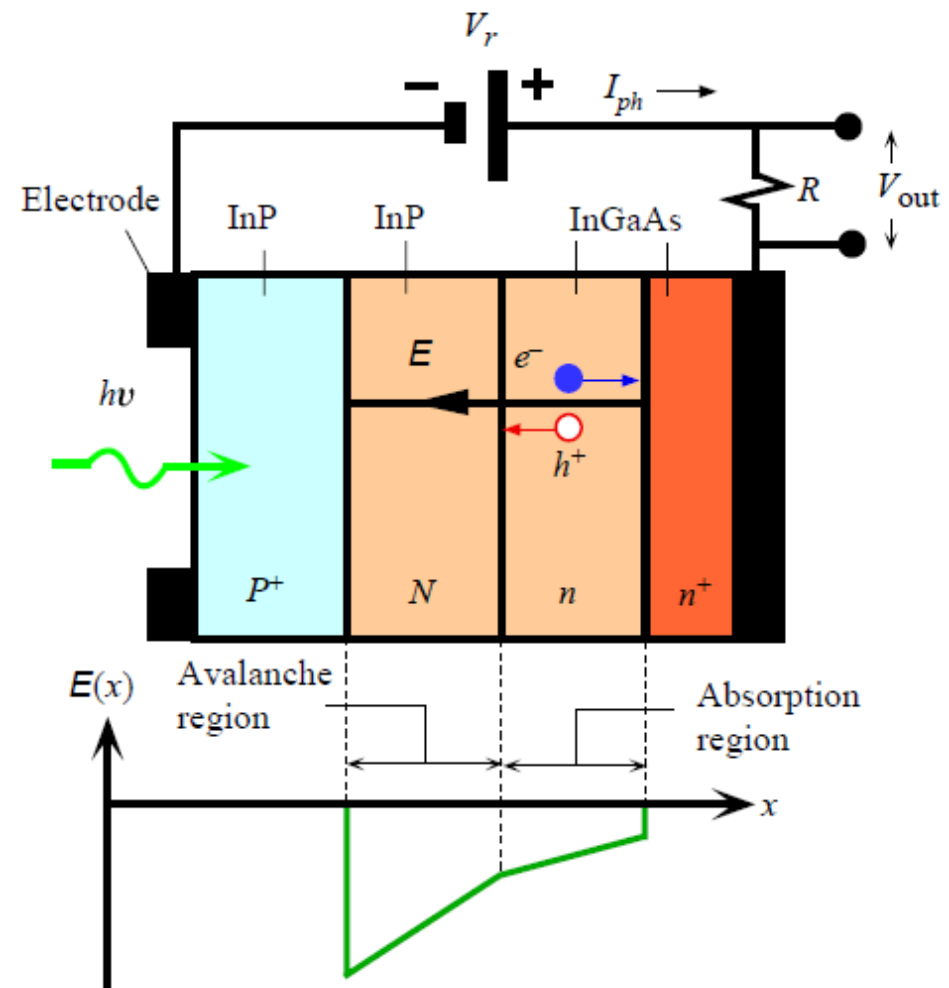


(c)



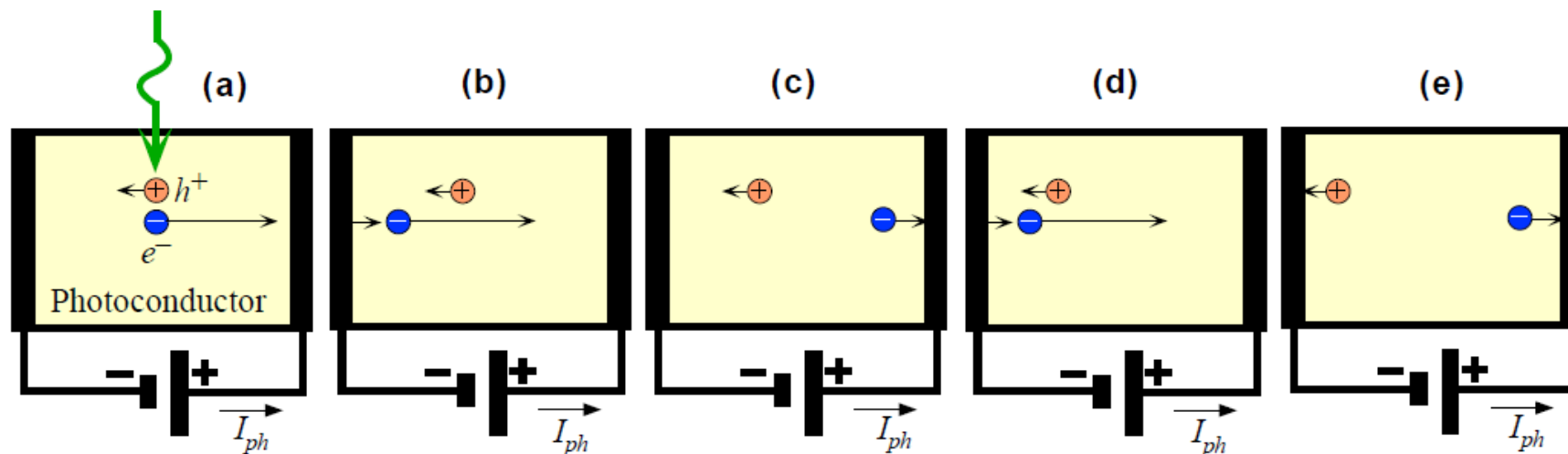
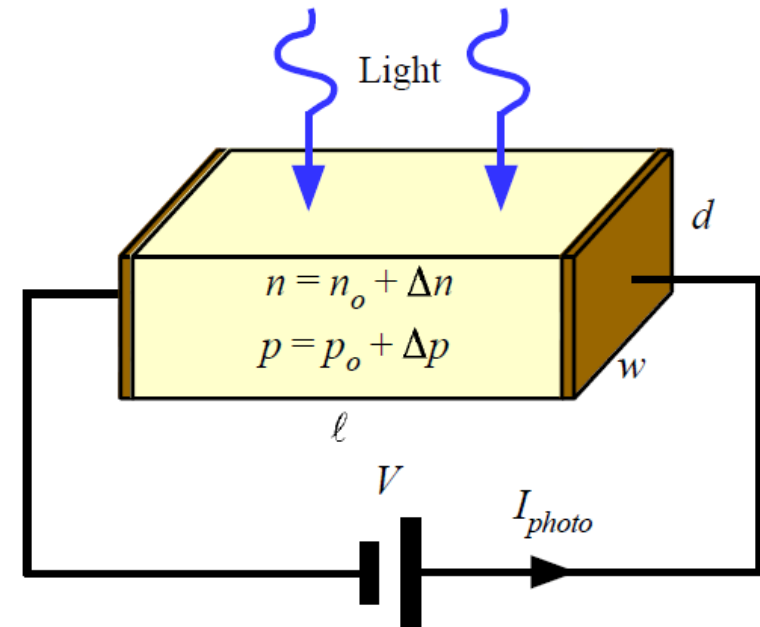
Heterojunction PDs

- $E_{g, \text{InP}} > E_{g, \text{InGaAs}}$
- Holes multiplied through avalanche process



Photoconductive PDs

- No junction
- Photoconductive gain
 - Electron mobility very fast
 - Charge neutrality needs be maintained





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- Concept of semiconductor and energy bandgap
 - pn junction
 - Photodetector types
 - Quantum efficiency



Responsivity (R)

- Quantum efficiency

$$\eta = \frac{\text{\# of free e-h pairs}}{\text{\# of input photons}} = \frac{I_{ph} / q}{I_0 / h\nu} < 1$$

$$R = \frac{I_{ph}}{I_0} = \eta \frac{q}{h\nu}$$

Responsivity (A/W)

